Docket No.: 51876P377

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of:

SUNG-KWON LEE

Art Group

Application No.:

Examine

Filed:

For: METHOD FOR FABRICATING

SEMICONDUCTOR DEVICE USING ARF
PHOTOLITHOGRAPHY CAPABLE OF
PROTECTING TAPERED PROFILE OF HARD

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INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure, enclosed is a copy of Information Disclosure Statement by Applicant (form PTO/SB/08), which is being submitted concurrently with the Utility Application. It is respectfully requested that the cited references be considered and that the enclosed copy of PTO/SB/08 be initialed by the Examiner to indicate such consideration and a copy thereof returned to applicant(s).

The submission of this Information Disclosure Statement is not to be construed as a representation that a search has been made in the subject application and is not to be construed as an admission that the information cited in this statement is material to patentability.

Please charge any fees due to Deposit Account 02-2666. A duplicate copy of the Fee Transmittal (PTO/SB/17) is enclosed for this purpose.

Respectfully submitted,

BLAKELY, SOKOLOFF, TAYLOR & ZAFMAN LLP

Date: (17/103

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12400 Wilshire Blvd., 7th Floor Los Angeles, California 90025 (310) 207-3800

Substitute for form 1449A/PTO INFORMATION DISCLOSURE		Complete if Known			
		Application Number	T		
		Filing Date			
STATEMENT BY APPLICANT (use as many sheets as necessary)			ICANT	First Named Inventor	Sung-Kwon LEE
				Art Unit	1
				Examiner Name	
Sheet	1	of	1	Attorney Docket Number	51876P377

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	U.S. PATENT DOCUMENTS					
Examiner	Cite	Document Number	Publication Date or Issue Date	Name of Patentee or	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
Initials*	No.1	Number - Kind Code ² (if known)	MM-DD-YYYY	Applicant of Cited Document	Figures Appear	
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		US-6,479,391 B2	11-12-2002	Morrow et al.		
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	Initial if reference considered, whether or not citation is in conformance with MPEF form with next communication.	609. Draw line through citation if not in conformance and not considered. Include

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Based on PTO/SB/08A (08-03) as modified by Blakely, Solokoff, Taylor & Zafmen.(wir) 08/11/2003.

Examiner